

REMARKS

Claims 1-26 are all the claims pending in the application.

Applicants note with appreciation that claims 16-22 are allowed.

The Examiner states that claims 23-26 are allowable, but objected to as depending from a rejected base claim.

Applicants note that claim 26 depends on claim 16, which the Examiner has indicated is allowed. Therefore, claim 26 is likewise allowable as written.

Claims 23-25 have been amended to be in independent form. Therefore, as indicated by the Examiner, claims 23-25 are in condition for allowance.

Claims 1-15 are rejected under 35 U.S.C. §103(a) based on Suwa (EP 789,278). In particular, in the Advisory Action dated October 9, 2002, the Examiner appears to agree that Applicants have presented evidence of unexpected superiority states, but that "upon further consideration of the comparative data," the comparative data is not commensurate in scope with the instant claims. The Examiner further states that the data compares the use of a fluorine containing surfactant with a non-fluorine containing surfactant, but fails to show the use of a silicon containing surfactant.

Applicants have amended independent claims 1, 2 and 9 to recite "at least one fluorine-containing surfactant." Therefore, Applicants respectfully submit that the claimed invention is commensurate in scope with the comparative data.

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Entry of this amendment is requested. The instant amendment was necessitated by the Examiner's issue of "further consideration of the comparative data" in the Advisory Action dated October 9, 2002 and thus could not have been presented earlier.

For the above reasons, and for the reasons of record, it is respectfully submitted that the subject matter of claims 1-15 is neither taught by nor made obvious from the disclosures of Suwa and it is requested that the rejection under 35 U.S.C. §103(a) be reconsidered and withdrawn. Applicants respectfully submit that this case is in condition for allowance and allowance is respectfully solicited.

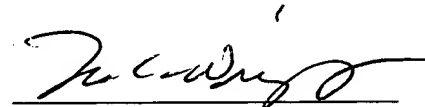
If any points remain at issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the local exchange number listed below.

Applicants hereby petition for any extension of time which may be required to maintain the pendency of this case.

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The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



Lee C. Wright
Registration No. 41,441

SUGHRUE MION, PLLC
Telephone: (202) 293-7060
Facsimile: (202) 293-7860

WASHINGTON OFFICE



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PATENT TRADEMARK OFFICE

Date: December 10, 2002

APPENDIX
VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

The claims are amended as follows:

1 (amended). A positive photosensitive resin composition comprising:

- (A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,
- (B) a compound which generates an acid upon irradiation with actinic rays,
- (C) a nitrogen-containing basic compound, and
- (D) at least one of a fluorine-containing surfactant [and a silicon-containing surfactant].

2 (twice amended). A positive photosensitive resin composition comprising:

- (A) a polymer which has bridged alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,
- (B) a compound which generates an acid upon irradiation with actinic rays,
- (C) a nitrogen-containing basic compound,
- (D) at least one of a fluorine-containing surfactant [and a silicon-containing surfactant], and
- (E) a solvent;

wherein the ratio of (B) to (C) by weight is from 5 to 300 and the ratio of (A) to (D) by weight is from 500 to 20,000.

9 (twice amended). A positive photosensitive resin composition comprising:

(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali-soluble,

(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound,

(D) at least one of a fluorine-containing surfactant [and a silicon-containing surfactant], and

(E) a solvent comprising as a first solvent at least one solvent selected from the following group (a) in an amount of 60 to 90 % by weight based on the total solvent and as a second solvent a solvent selected from the following group (b) in an amount of 10 to 40 % by weight to the total solvent; the group (a) consisting of ethyl lactate, propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether propionate, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate, and the group (b) consisting of solvents having a viscosity of not higher than 1 centipoise at 20°C.

Claim 23 (twice amended). [The] A positive photosensitive resin composition [as claimed in claim 1] comprising:

Claim 23 (twice amended). [The] A positive photosensitive resin composition
[as claimed in claim 1] comprising:

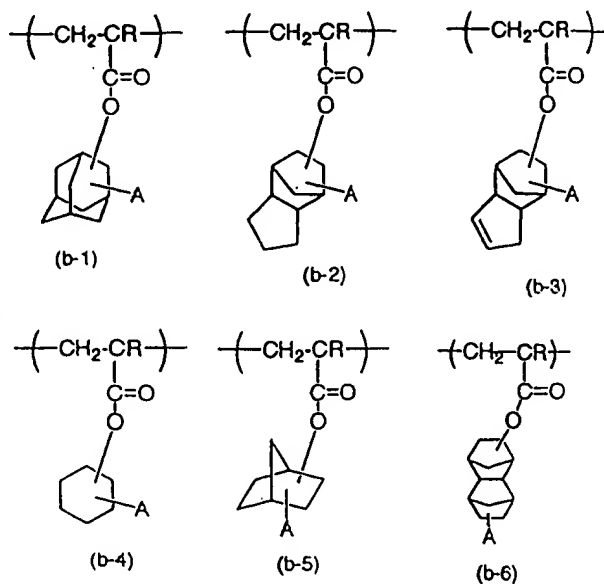
(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes
by the action of an acid to thereby become alkali-soluble,

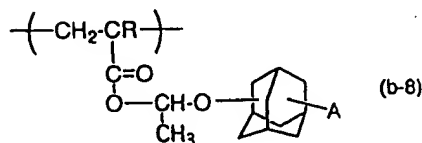
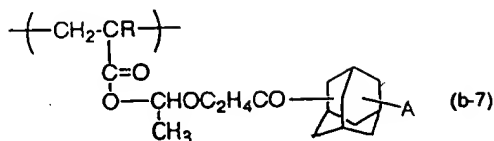
(B) a compound which generates an acid upon irradiation with actinic
rays,

(C) a nitrogen-containing basic compound, and

(D) at least one of a fluorine-containing surfactant and a silicon-containing
surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and
decomposes under the action of an acid to become alkali soluble contains a
repeating unit selected from the group consisting of repeating units having the
structural formulas (b-1) to (b-8):





wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxycarbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from 1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.

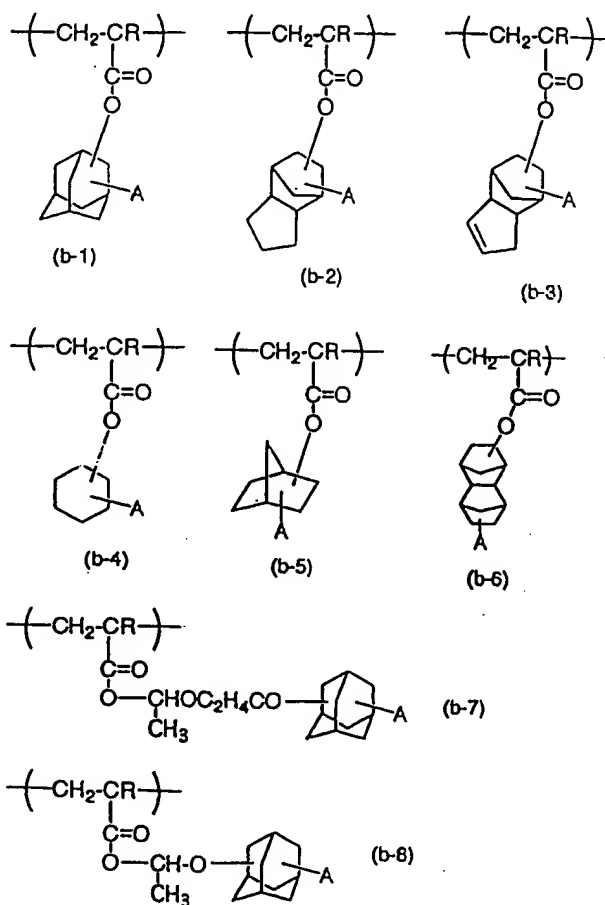
Claim 24 (twice amended). [The] A positive photosensitive resin composition [as claimed in claim 2] comprising:

(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,

(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound, and
(D) at least one of a fluorine-containing surfactant and a silicon-containing surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):



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wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxycarbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from 1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.

Claim 25 (twice amended). [The] A positive photosensitive resin composition [as claimed in claim 9] comprising:

(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,

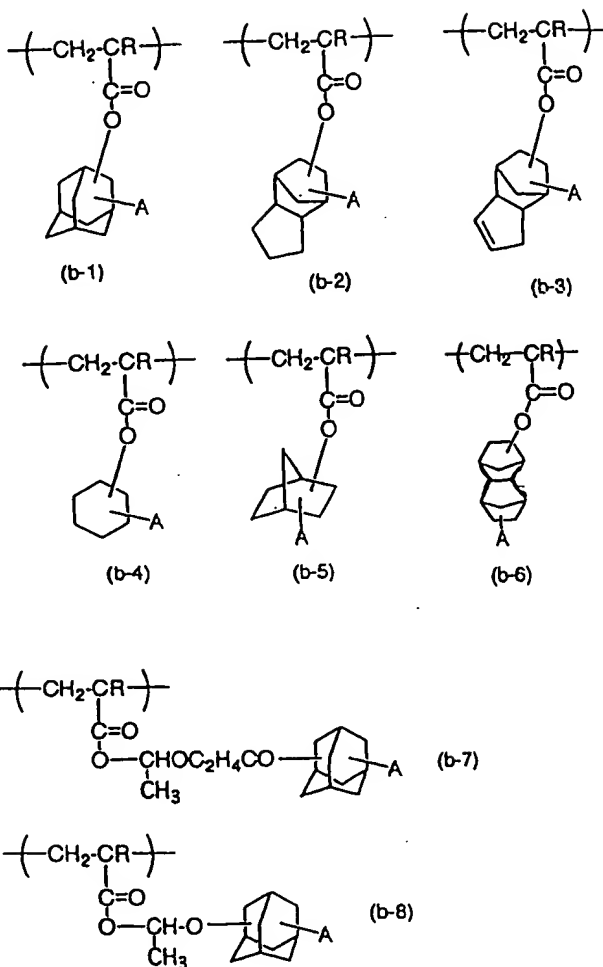
(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound, and

(D) at least one of a fluorine-containing surfactant and a silicon-containing surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):

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wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxycarbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from

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1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.